Discharging of Dielectric Materials as Related to Secondary Electron Emission Nikola Protic (Cornell University), advised by Professor Yevgeny Raitses (Princeton Plasma Physics Laboratory)

Motivation

- Refinement of Plasma-Wall Sheath model to account for wall charging by plasma and secondary electron emission fluxes.
- Gain insight into space charge distribution of the plasma-facing wall
- Development of a SEE model which accounts for charging effects

Background: SEE and Charging

• Electron bombardment of dielectrics can result in both positive or negative charging depending on incident electron energy, due to secondary electron emission:



• A quantitative three step model has been proposed for SEE; however, the model fails to account for space charge on the wall surface:

$$\delta(E_0, Q) = \int_0^{R(E_0, Q)} n(x, Q; E_0) \cdot f(x, Q; E) \cdot B(E, Q) dx$$

• To study surface charging insight can be taken from refinement of the plasma-wall potential:

electron surface layer



• Ab initio studies of discharging have been conducted, but conclusions have yet to be reached:



Idea: Discharging of the charged surface by a biased contact.

- Al₂O₃ Sample is bombarded by a Kimball Physics Inc. ELG-2 Electron Gun in 5 μ s pulses.
- Sample is rotated and placed in contact with a discharger
- Discharging is monitored independently by measuring the discharger current and relative pulse response after discharging.

- Noise source causing ~50 kHz & ~7kHz beating noise over all channels
- All channels experiencing pickup from an external source (ground loop through bias source).
- A solution: Collect desired signal & pickup signal simultaneously, post process in MATLAB using Fourier techniques.
- Both Phase Filtering and Notch Filtering attempted with limited success.





Partial Discharge is Bias-Dependent

Modeled charging as disk above grounded plane in order to estimate number of pulses until yield reaches unity (space charge saturation):

$$V \approx \frac{\sigma_{dep}(N_p)}{2\epsilon_0} \Big[\sqrt{(z+d)^2 + R^2} - \sqrt{(z-d)^2 + R^2} - 2d \Big] \approx 6V \text{ per}$$

$$\Rightarrow 50 \text{ mulses to saturation}$$

 \rightarrow 50 pulses to saturation Experimentally, pulse signal attenuated by 1/e in 13 pulses. Concluded that

$$I(N_p) = I_0 e^{-i p/20}.$$

- Summing above equation, total charge deposited is about 34 pC.
- Observed incomplete discharging. Discharging reached difference non-neutral steady states depending on discharger bias.
- Indicates space charge depth distribution & work function dependence. \bullet
- From Fick's Law and Ohms Law diffusion current was roughly estimated to be on the order of femtoamperes, indicating that diffusion is not involved at room temperature.

Contact Discharging is a threshold phenomenon

- Both fast and slow discharging of surface observed under various conditions.
- Fast Discharging observed as a threshold phenomenon: under low discharger biases no contact signal observed.
- Slow Discharging observed only for low (< |+/-18 V|) applied biases.
- Indicates a distribution of electrons by depth into the material.
- Likely that slow discharging is a thermally-mediated mechanism for bulk discharging.